Angelo Rivetti

# Future trends, challenges and opportunities in ASICs for HEP

a birds-eye view



Istituto Nazionale di Fisica Nucleare

## **Overview**



- Relevant non-HEP related trends
- Relevant HEP ASICs trends and perspectives
- Some "experienced-based" remarks

## **Common features of ASICs for HEP**



- We need ASICs mostly for front-end, power management, data transmission;
- High resolution timing is becoming a must for many detectors;
- Finer granularity (but not so extreme), less power
- In (inner) layers of hadron colliders, life is complicated by radiation damage, which imposes lengthy technology testing procedure;
- We are adding cold ASICs to the menu;
- Production volumes are, at best, very modest compared to industry standard;
- HEP ASICs are very specific systems fabricated in mainstream technologies built out of very common critical blocks (ADCs, TDCs, PLLs, DLLs, Power converters, ser-des, etc..)

## Key IPs: ADCs

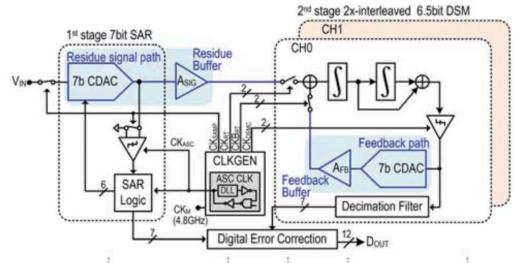


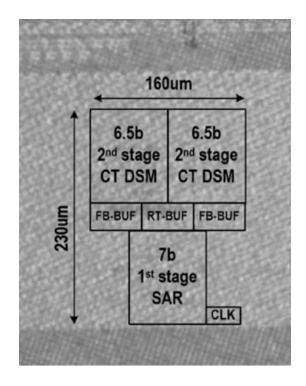
### **ISSCC 2021**

#### 10.5 A 12b 600MS/s Pipelined SAR and 2×-Interleaved Incremental Delta-Sigma ADC with Source-Follower-Based Residue-Transfer Scheme in 7nm FinFET

Seungyeob Baek, Ilhoon Jang, Michael Choi, Hyungdong Roh, Woongtaek Lim, Youngjae Cho, Jongshin Shin

Samsung Electronics, Hwasung, Korea





Power: 13 mW

Very good performance ADC in many different technology nodes Extremely scaled nodes may bring density more than low power

## **Key IPs: ADCs**



IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 55, NO. 2, FEBRUARY 2020

### A Temperature-Stabilized Single-Channel 1-GS/s 60-dB SNDR SAR-Assisted Pipelined ADC With Dynamic Gm-R-Based Amplifier

Wenning Jiang, *Student Member, IEEE*, Yan Zhu<sup>®</sup>, *Member, IEEE*, Minglei Zhang<sup>®</sup>, *Member, IEEE*, Chi-Hang Chan<sup>®</sup>, *Member, IEEE*, and Rui Paulo Martins<sup>®</sup>, *Fellow, IEEE* 

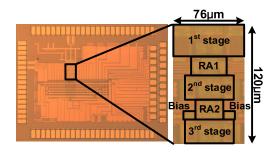


TABLE II ADC Performance Summary and Comparison

	This work	VLSI 2017[16] KJ. Moon	JSSC 2018[3] R. Sehgal	ISSCC 2017[9] L. Kull	ISSCC 2017[17] H. Huang	ISSCC 2019[25] B. Hershberg	JSSC 2019[4] J. Lagos
Architecture	Pipelined SAR	Pipelined SAR	Pipeline	Pipelined SAR	Pipelined SAR	Pipeline	Pipeline
Residue Amplifier	Open-loop Gm-R	gm-cell	Open-loop Integrator	CML Amplifier	Dynamic Amplifier	Ring Amplifier	Ring Amplifier
Technology	28nm	28nm	28nm	14nm	65nm	16nm	28nm
Resolution [bits]	12	10	12	10	12	11	12
Sample Rate [MS/s]	1000	500	280	1500	330	600	1000
Supply Voltage [V]	1	1	1	0.95	1.3	0.85	0.9
SFDR @Nyq. [dB]	74.56	69.2	77	58.39	75.8	78.3	73.1
SNDR @Nyq. [dB]	60.02	56.6	64	50.1	63.5	60.2	56.6
Power [mW]	7.6	6	13	6.92*	6.2	6.0	24.8
FoM <sub>walden</sub> @Nyq. [fJ/conv-step]	9.28	21.7	35.8	17.7*	15.4	12	45
FoM <sub>Schreier</sub> @Nyq. [dB]	168.2	162.8	164.3	160.5*	167.8	167.2	159.6
Area [mm²]	0.0091	0.015	0.22	0.0016	0.08	0.037	0.54

\* including the reference buffer

## **Key IPs: ADCs**

IEEE TRANSACTIONS ON CIRCUITS AND SYSTEMS-I: REGULAR PAPERS, VOL. 68, NO. 2, FEBRUARY 2021

### A 91.0-dB SFDR Single-Coarse Dual-Fine Pipelined-SAR ADC With Split-Based Background Calibration in 28-nm CMOS

Yuefeng Cao<sup>10</sup>, Member, IEEE, Shumin Zhang<sup>10</sup>, Tianli Zhang<sup>10</sup>, Member, IEEE, Yongzhen Chen<sup>(D)</sup>, Member, IEEE, Yutong Zhao<sup>(D)</sup>, Chixiao Chen<sup>(D)</sup>, Member, IEEE, Fan Ye<sup>®</sup>, Member, IEEE, and Junyan Ren<sup>®</sup>, Member, IEEE

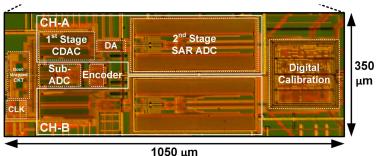


TABLE II COMPARISONS TO OTHER DESIGNS WITH COMPARABLE SAMPLING RATE AND RESOLUTION

			Dither		X					
		Kapusta JSSC'13 <sub>Vin</sub> [41] <sub>N_B=</sub>	Goes	Akter JSSC'18 [42]	A Xu JSSC'19 [22]	Hung CICC'19 • x <sub>out</sub> []] x <sub>A</sub> +x <sub>B</sub> )/2	Seo VLSI'19 [44]	Liu ISSCC'20 [45]	Zhang ESSCIRC'19 [24]	This work
Process	(nm)	65	28	40*	65	90	40	40	28	28
Resolution	n (bits)	14	Injuction V	+∆V→12 CH	B 4	16	12	13	14	14
f <sub>s</sub> (MS	/s)	80	80	53	75	40	200	40	60	60
Supply volt	age (V)	1.2	1.0	1.0	1.2	1.1	0.9	-	1.05	1.05
Core area	$(mm^2)$	0.55	0.131	0.76	0.342	0.506	0.026	0.005	0.28	0.368
Calibra	tion	analog	analog + statistical	analog + split-ADC	split-ADC+ LMS	no calib.	no calib.	-	split-ADC+ ML	split-ADC+ LMS
	@ low fin	73.6	68	-	77.8	72.6	61.1	70.8	66.2	66.9
SNDR (dB)	@ Nyq.	71.3	66	66	70.8	71.2	62.1	69	63.9	64.1
SFDR (dB)	@ low fin	-	80.7	-	92.1	-	65.2	86.5	93.7	91.0
SFDR (db)	@ Nyq.	88.6	74.0	77.3	89.6	86.8	67.1	79.2	83.3	84.1
Power (1	nW)	31.1 *	1.5	9*	24.9 * <sup>&amp;</sup>	5.5 *	3.9	0.591	2.79	4.26 *#
FoM <sub>s</sub> (dB)	@ low fin	164.7	172.3	-	169.6	168.2	165.2	176.1	166.5	165.4
$\Gamma OIM_S (UD)$	@ Nyq.	162.4	170.3	160.7	162.6	166.8	166.2	174.3	164.2	162.6
FoM <sub>w</sub>	@ low fin	99.4	9.1	-	52.3	39.4	21.0	5.2	27.9	39.3
(fJ/convstep)	@ Nyq.	129.5	11.5	104.1	117.2	46.3	19.0	6.4	36.3	54.2
$FoM_s = SNDR$	$+10*\log_{10}(f_s)$	/2/Power); F	$oM_W = Power$	$r/(f_s*2^{ENOB}).$						

\* including clock buffer

<sup>&</sup> including reference buffer

<sup>#</sup> including digital calibration

- Very good performance ADC in many different technology nodes
- External nodes may bring density more than low power

## A word on ADC architectures



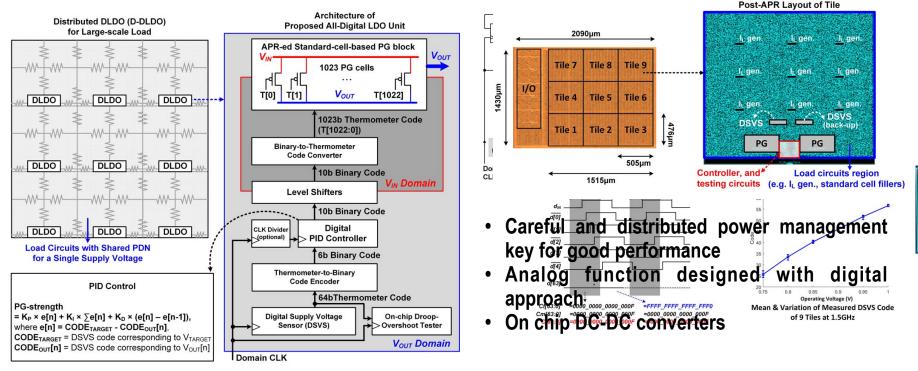
- While technology has clearly a role, architectures have their share, too
- Many architectures employ SAR as main ADC or as a sub-unit
- Key changes in SAR topologies occurred 10-12 years ago the allowed much higher speed and low power (50 MS/s, 1 mW, 10 bit in 130 nm)
- If such architecture were there 10 years before, chip designed for LHC in 250 nm might have looked significantly different...



## 25.1 A Fully Synthesizable Distributed and Scalable All-Digital LDO in 10nm CMOS

Suyoung Bang, Wootaek Lim, Charles Augustine, Andres Malavasi, Muhammad Khellah, James Tschanz, Vivek De

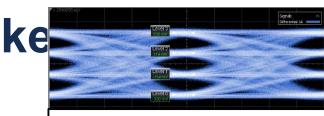
Intel, Hillsboro, OR

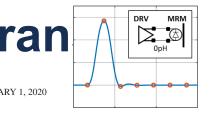


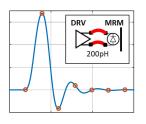
tie 284 Veltal Hundlers Tag Display Carsors Massure Mask Math MyScope Analyse Utilities Hep 💶	Tek 🚍 🔀 🕫 🛙	R Vertical Hondrico Tag Daping Cursors Measure Mask Math MyScope Anal	par Ulilles Map 💽 🛛 Tek 🚍
V <sub>OUT</sub> (0.840V)		V <sub>оџт</sub> (0.840V)	
\$100	mV/div		\$100mV/div



**ISSCC 2020** 

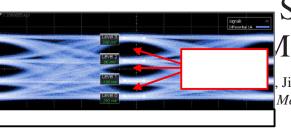






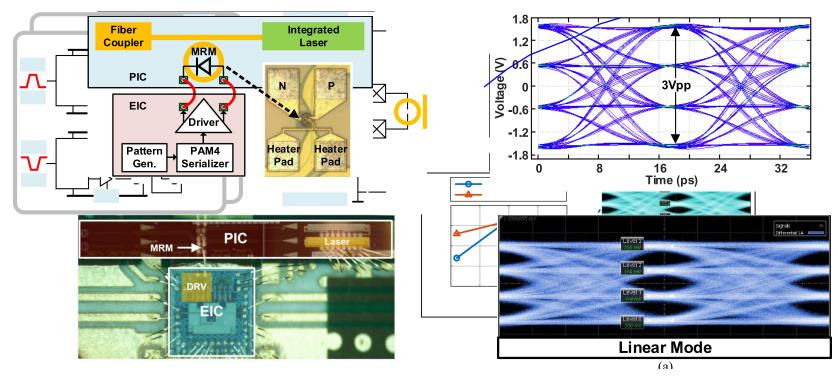


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### Silicon Photonics Transmitter /Iodulator and CMOS Driver

, Jie Sun<sup>®</sup>, Jeffery Driscoll, Ranjeet Kumar<sup>®</sup>, Hasitha Jayatilleka<sup>®</sup>, *Member, IEEE*, James Jaussi, and Bryan Casper



## 28 nm + Silicon Photonics

Ծաւթաւ շծաշ

# Key IPs: TDC. 8. INL of proposed CB-VDL TDC.

### A 0.6 V, 1.74 ps Resolution Capacitively Boosted Time-to-Digital Converter in 180 nm CMOS





Arjun Ramaswami Palaniappan<sup>1,2</sup> and Liter Siek<sup>1</sup>

<sup>1</sup>School of Electrical and Electronic Engineering, VIRTUS, Nanyang Technological University, Singapore 639798, Singapore <sup>2</sup>NXP Semiconductors, Singapore 138628, Singapore

Email: arjun011@e.ntu.edu.sg

TDC	Proposed <sup>a</sup>	[16]	[17]	[18]	[15]
Architecture	Cap Boost VDL	Stoch	Time Amp	Cyclic	Pipeline
Process	180 nm	14 nm	65 nm	0.35 µm	65 nm
Supply (V)	0.6	0.6	1.2	3.3	1.2
Power (mW)	0.217	0.78	2	80	15.4
Range (bits)	6	10	8	13	9
Resolution (ps)	1.74	1.17	2.6	0.61	1.12
INL (LSB)	1.45	2.3	2.36	7.38	1.7
$F_s$ (MHz)	50	100	80	0.8	250
FOM (pJ/con.step)	0.166	0.025	0.328	102.3	0.325
Area (mm <sup>2</sup> )	1.225 <sup>b</sup>	0.036	0.07	0.61°	0.14

#### TABLE I.PERFORMANCE COMPARISON OF TDC DESIGNS

Timing resolution defined at the interplay between the sensor and the very front-end

<sup>a.</sup> Simulated results

<sup>b.</sup> On-chip calibration

<sup>c.</sup> Off-chip calibration

## How small can be a

## 7.9 1/2.74-inch 32Mpixel-Prototype CMOS Image Sensor with 0.64 $\mu$ m Unit Pixels Separated by Full-Depth Deep-Trench Isolation

JongEun Park, Sungbong Park, Kwansik Cho, Taehun Lee, Changkyu Lee, DongHyun Kim, Beomsuk Lee, SungIn Kim, Ho-Chul Ji, DongMo Im, Haeyong Park, Jinyoung Kim, JungHo Cha, Taehoon Kim, In-Sung Joe, Soojin Hong, Chongkwang Chang, Jingyun Kim, WooGwan Shim, Taehee Kim, Jamie Lee, Donghyuk Park, EuiYeol Kim, Howoo Park, Jaekyu Lee, Yitae Kim, GungChak Ahn, YoungKi Hong, ChungSam Jun, HyunChul Kim,

Items	unit	0.7um	0.64um
Linear FWC	e-	6,000	6,000
Dark current	e-/s	1.3	1.1
White spot <sup>1)</sup>	ppm	10	15
Random noise	e-	1.4	1.4

400

Output [DN]

600

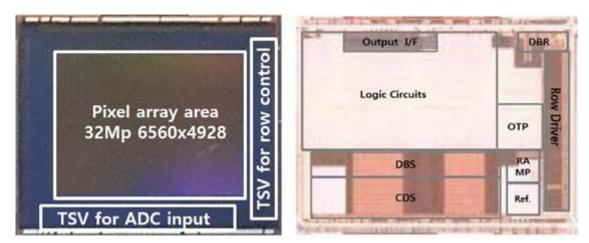
800

KELL

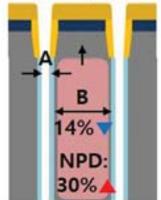
0.1

0

200



0.64µm

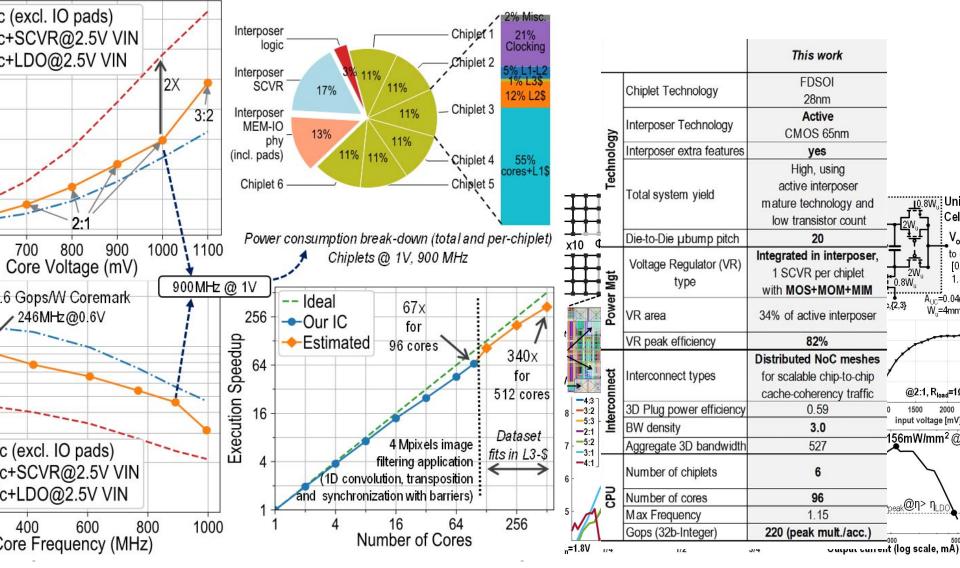


ridth Density	0.5	3.0	1.6	Tb/s/mm <sup>2</sup>
n Cross Section	0.9	N/A	0.8	Tb/s/mm
e inter-Chiplets	394	133		OD/n
andwidth	52	27	640	GB/s

End to end latency	7.2	44.0	15.2
Propagation speed	4.8	2.9	0.6
Energy/bit/mm	0.29	0.15	0.52



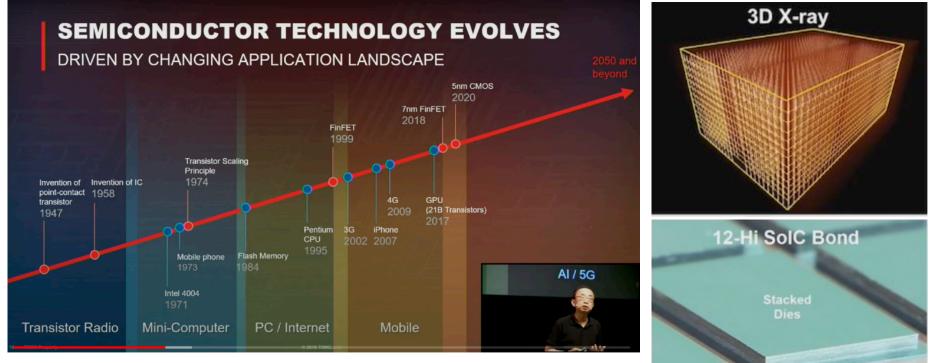




## **Moore after Moore**



#### https://www.youtube.com/watch?v=O5UQ5OGOsnM



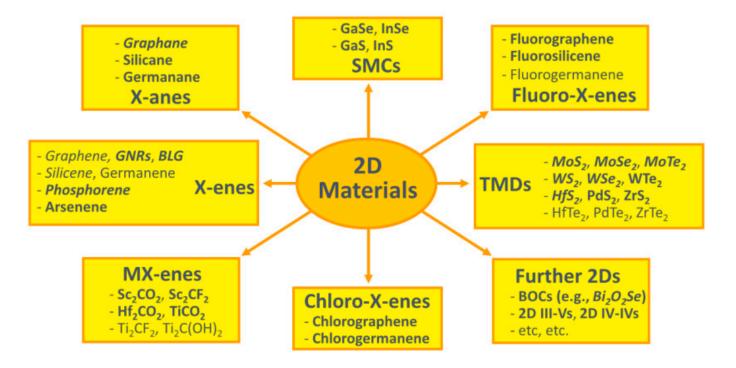
P. Wong, TSMC Vice President for R&D: "Moore law is not dead, it is not even sick!"

- Moore laws may continue due to 3D integration and new devices
- New technologies may surprise us and open unexpected possibilities

# New materials being investigated



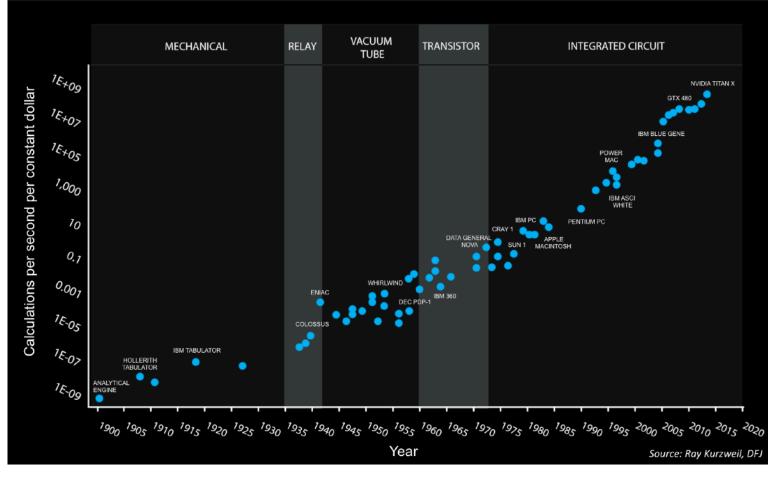
*Nanomaterials* **2020**, *10*, 1555



## **Moore before Moore**



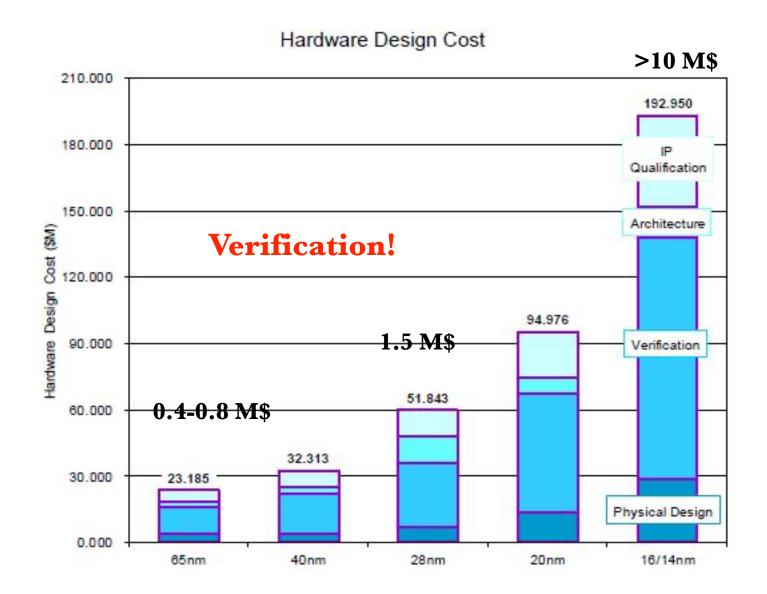
## 120 Years of Moore's Law



https://upload.wikimedia.org/wikipedia/commons/6/62/Moore%27s\_Law\_over\_120\_Years.png

## **IC economics**





# Technology may also saturate (at least for a long while...)

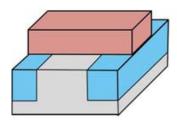




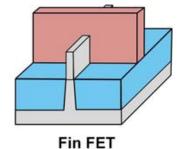
• because of physics...

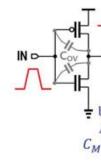


• ... cost



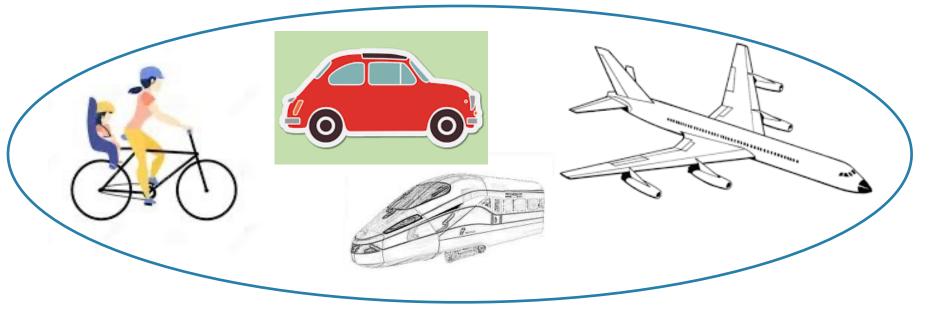
Planar FET





# Technologies can coexist for an indefinite time





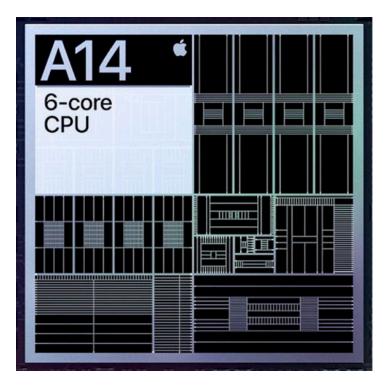
#### https://europractice-ic.com/schedules-prices/schedules-2021-2/



 Two order of magnitudes in transistore gate length (and in price): from 0.7 um (at 300 eur/mm<sup>2</sup>) to 12 nm (26.000 eur/mm<sup>2</sup>)

## One extreme...





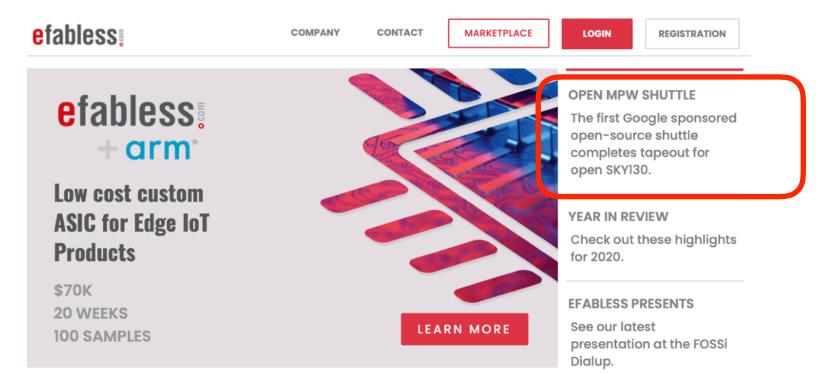
- 5 nm technology
- Exa-core
- 64 bits
- Neural engine
- 11.8 billions transistors
- 88 mm<sup>2</sup>
- 130 millions transistors/mm<sup>2</sup>

- In a typical mobile SoC: 60% logic, 30% RAM, 10% analog
- In comparison, we have onboard our chips just a bit of logic...





### https://efabless.com

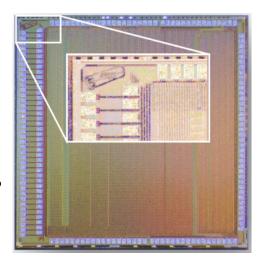


### https://www.skywatertechnology.com

## **Technology wrap-up**



- There are much more opportunities than what we can possibly explore
- Average technology node life-time proved to be much longer than imagined in the past
- Choosing a technology, to some extent, is always a bet
- No particular concerns on performance achievable for key IP blocks in very advanced nodes
- What you really buy is density, speed and power for digital components and you should use it
- R&D on most advanced nodes should be definitely supported
- The key issue is to have enough engineers to work out the best of it to our needs
- E.g. 9 mm2 in 12 nm = 234 k euros= 20.000.0000 transistors. What do you do with that!?



- 110 nm technology
- 5 mm x 5 mm
- 64 channels
- 10 bits ADC, 50 ps TDC per channel
- 30 keuros for protoyping, 170 keuros for production

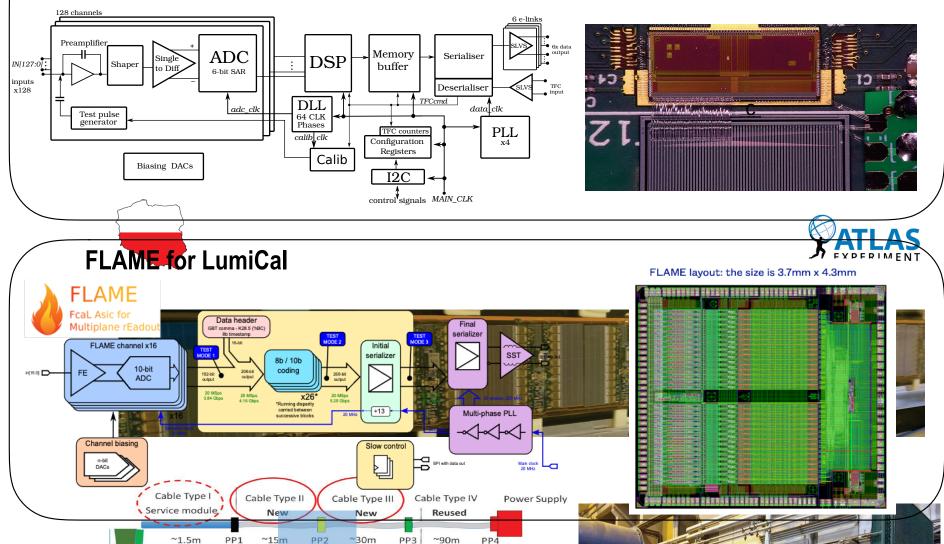
We need to move, but we should not be in a hurry Take the time to think...

## **Trends in ASICs for HEP**



### **Present/near term**

### SALT: 128 ch. ASIC for strip readout in LHCb - M. Idzik, TWEPP 2019



## **Trends in ASICs for HEP**



### Likely evolution in multi-purpose ASICs

- Include also TDC for timing
- Higher resolution, flexible ADCs
- Fully fledged on board DSP
- High granularity on board power management
- Looks very promising for advanced nodes

### How much intelligence do we need on chip?

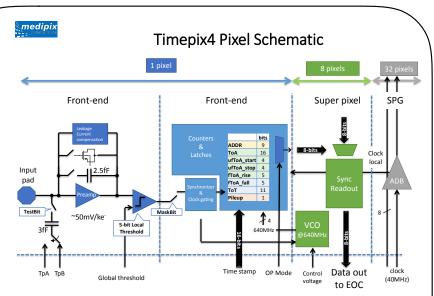
- In very advanced node it is natural to have more processing power
- Exact partitioning between on-board and off-detector signal processing to be determine with detailed detector studies
- Fully fledged on board DSP
- High granularity on board power management

## Trends in ASICs for HEP: hybrid pixels



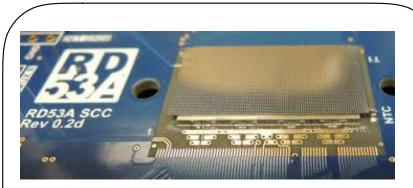
### **Present/near term**

### TimePix4



- Time resolution 200 ps
- 55 micron pixel pitch
- 4 sides buttable with TSV
- 3.5 MHit/mm<sup>2</sup>/s
- 65 nm CMOS

### **RD53 series**

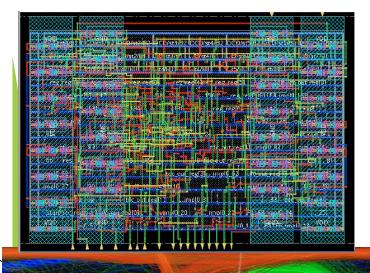


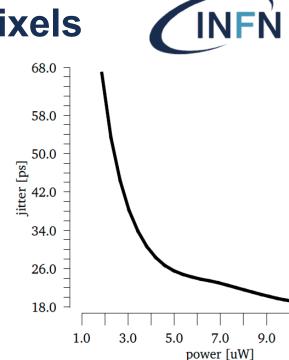
- Common baseline development
- Final chips customised in some details
- 50 x 50 um pixels
- > 1 GHz/cm2
- 65 nm CMOS

# Trends in ASICs for HEP: hybrid pixels

### Likely future evolutions

- Reduced pixel cells (towards 25 um x 25 um @FCC-hh
- Move to more scaled technology nodes: 28 nm, ??
- High time resolution per pixel (< 100 ps)
- New interconnection technologies: high performance
- More processing on chip



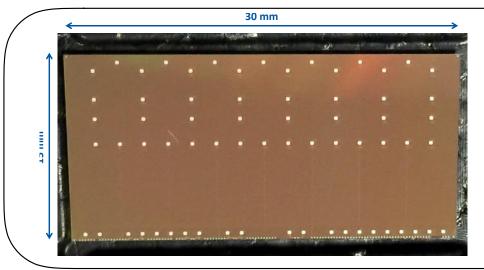


- TDC on the INFN Timespot ASIC
- 55 um x 55 um pixels
- TDC size 22 um x 15 um
- Real time time-walk correction
- 28 nm CMOS

## **Trends in ASICs for HEP: monolithic**



### State of the art



### Likely future evolutions

- Ultra-thin, wrap-around CMOS sensors
- Beyond reticle size with stitching
- Fully depleted CMOS
- CMOS sensors with timing capabilities
- Due to 3D integration, monolithic and hybrid may converge in high performance solutions
- In outer layers lots of 2D CMOS sensors

- 180 nm CMOS
- Sparsified readout
- 28 um x 28 um pixels
- 24000 sensors for 10 m2

## **Final thoughts**



- Accelerators are expected to follow an evolutionary approach: requirements in ASICs rather clear even for the very far future;
- In term of technology, only problematic case: FCC-hh at < 40 cm: but we have some time ahead
- For the rest, it is mostly a question of budgets
- Biggest issues will not be technology per se, but costs at large
- We need to profit more by the latest advances in CAD tools, which are tuned to chip extremely more complex that the ones we typically need to develop
- Promote collaboration more than competition (e.g. avoid "parallel options")
- Incorporate early realistic ASICs description in detector simulations
- Open ecosystem of IPs
- For full size ASICs have teams of appropriate size (both too large and too small can be a problem) with roles and tasks
- Multilateral funding implies multilateral teams